



#### **FBK SiPM technology**

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Sep 12, 2019



#### Fondazione Bruno Kessler



Detector-grade clean-room, 6 inches, class 10 and 100



Silicon Photomultipliers account for a significant portion of the detectors fabricated here.

Publicly funded research center

350 researches working in different fields

In addition, we have proven experience (e.g. with CERN) in Strip Detectors, Pixel Detectors and Silicon Drift Detectors (state of the art)





#### Outline

- SiPM technology at FBK
  - NUV-HD technology
  - Performance improvements
  - Crosstalk reduction
  - Primary DCR reduction
  - VUV-HD
  - Position sensitive SiPMs
  - Radiation hardness of SiPMs
- Single photon time resolution
  - SPTR: factors affecting single SPAD performance
  - SPTR: factors affecting SiPM performance

# **FBK SiPM technology roadmap**



# **NUV-HD Technology**







- p-on-n junction → Higher trigger probability for NUV light
- Narrow dead border region (< 2  $\mu$ m)  $\rightarrow$  Higher Fill Factor
- Trenches between cells  $\rightarrow$  Lower Cross-Talk



### **NUV-HD: Fill Factor**





SPAD Pitch	15 µm	20 µm	25 µm	30 µm	35 µm	40 µm
Fill Factor (%)	55	66	73	77	81	83
SPAD/mm <sup>2</sup>	4444	2500	1600	1111	816	625
High Dynamic	<b>↓</b> Range, F	ast recov	very time	-	High PDI	
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# **Show Photon Detection Efficiency**



Gola, A et al. (2019). "NUV-Sensitive Silicon Photomultiplier Technologies Developed at Fondazione Bruno Kessler." *Sensors*, *19*(2), 308.

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### Dark Count Rate and Direct Cross Talk



Dark Count Rate

Optical Crosstalk (Correlated Noise)



# **NUV-HD Improvements**



### NUV-HD-LowCT



Light absorbing material was inserted inside trenches, between adjacent microcells



SEM image of trenches, separating adjacent microcells.

Metal in trenches is under development..

**Applications** such as CTA





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# **SUBJECT NUV-HD – Reduction of DCR**

We are experimenting with technology splits to further reduce the noise (DCR).



New NUV-HD & VUV-HD SiPMs: 35µm and 40µm cell pitch

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#### VUV-HD

In some specific applications direct detection of VUV light is required → NUV-HD technologies have 2 main limiting factors



Typical ARC is a multi-layer stack of SiO<sub>2</sub>(absorbs  $\lambda$ <150nm), Si<sub>3</sub>N<sub>4</sub>(absorbs  $\lambda$ <250nm)  $\rightarrow$  external QE is affected



Ultra-shallow absorption of UV light in silicon: λ<sub>abs</sub><10nm at λ=300nm → generated e-h pairs have high recombination probability due to defects → internal QE is affected

R&D focused on ARC optimization:

- Si<sub>3</sub>N<sub>4</sub> removal
- Preservation of surface passivation quality

Current R&D has been conducted in collaboration with TRIUMF



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# Linearly-Graded SiPM (LG-SiPM)

- Linearly-Graded Silicon Photomultiplier
  - A type of position-sensitive silicon photomultipliers (PS-SiPM).
  - 4 cathode signals (position information) and 1 anode signal.
- The currents of the 4 cathode signals change linearly according to the position of the fired microcell.
- Position

$$x = \frac{L - R}{L + R} \qquad y = \frac{T - B}{T + B}$$

• Energy

$$E = L + R + T + B$$

Several microcells triggered





LG-SiPM



# 2 x 2 array of LG-SiPMs

- 2 x 2 array of 7.75 x 7.75 mm<sup>2</sup> LG-SiPMs
- Microcell size: 20 μm (square cells).
- Gap between LG-SiPMs is 0.2 mm.
- Application: small-animal PET





Gamma ray source

1.5 x 1.5 cm<sup>2</sup> 4 readout channels only

LYSO array 30 x 30 array of 0.445 x 0.445 x 20 mm<sup>3</sup> Pitch size is 0.5 mm.



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# **SiPM Radiation Hardness**

At FBK we are developing radiation hard SiPMs for HEP and spatial applications.

Effects of Radiation Damage	Mitigation techniques
Increased Primary Dark Count Rate	Electric field engineering
Increased Afterpulsing	Electric field engineering Process adjustments
Efficiency loss (due to cells busy at triggering dark noise)	Very high cell density Ultra-fast recharge time



Low Field NUV-HD SiPMs, 15 µm cell irradiated at 5x10<sup>13</sup> 1 MeV eq n/cm<sup>2</sup> Dark current per mm<sup>2</sup> at variable temperature FBK SiPMs already demonstrated capability of surviving > 5e13 1 MeV neq/cm2 irradiation dose.

More and more demanding specifications form HEP experiments required development of single-photon detectors with next-generation radiation hardness.



# Thank you! Any question?

Thanks to all the members of the team working on custom SiPM technology at FBK:

Fabio Acerbi Anna Rita Altamura Giacomo Borghi Massimo Capasso Andrea Ficorella Nicola Furlan Alberto Gola Stefano Merzi Vladimir Mozharov Giovanni Paternoster Veronica Regazzoni Nicola Zorzi

# "Time Resolution" Using SiPMs



#### 1) Single-photon time resolution (SPTR)

- LASER excitation; 1-photon triggers the SiPM
- Very important: SPAD internal structure!
   Signal amplitude! Noise of front-end electronics!





#### 2) <u>Time resolution for few-photon signals</u>

- Applications like Cherenkov detection, LIDAR
- Important: Noise of detector! Crosstalk between SPADs!

#### 3) <u>Time of arrival of high-energy gamma rays</u>

- Resolving the time-of-arrival of 1 gamma ray or 2 simultaneous gamma rays (coincidence resolving time, CRT)
- Many photons: large signals but threshold few ph. level.
- SiPM is coupled with scintillator → PDE important !
- Applications: ToF-PET / timing in HEP experiments

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# **Single Photon Time Resolution**





ACTIVE AREA LAYOUT	Diameter / side (µm)	Metallization
circular	20	Covered edges (A) with metal
circular	20	uncovered edges (B)
square	50	uncovered edges



1) <u>Worse charge collection at SPAD edges</u>

2) Signal pick-up is very important

<u>Covering the SPAD edges with</u> metal <u>reduces the SPTR to 20 ps</u>

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### SPTR of SiPMs: Effect of Dimension



→ larger SiPM metal capacitance

very important on med/big area SiPMs



# SPTR of SiPMs: Effect of Dimension $\sigma_n \propto \sigma_n$





Larger active area → larger SiPM metal capacitance Electronic noise effect on SPTR very important on med/big area SiPMs

### SPTR of SiPMs: Transit Time Skew



With med./large area SiPMs
→ important also the effect of transit time skew
→ depend on metal grid and bonding pads



Efficient signal pick-up and improved metal grid layout needed.